

## Erratum to: Thin Film Growth of Germanium Selenides from PECVD of $\text{GeCl}_4$ and Dimethyl Selenide

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Published online: 30 January 2011  
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### Erratum to: Plasma Chem Plasma Process DOI 10.1007/s11090-010-9278-8

In the online published article, it was neglected to note that the flow rates listed in the Table 1 for the DMSe flow were based on a nitrogen flow controller.

The nitrogen to DMSe flow rate conversion factor was not available for the MKS flow controller that was used. A conversion factor of 0.34 from a different flow controller manufacturer was recently found. The actual DMSe flow rate may be approximated by multiplying the table entry by 0.34. Thus for a flow rate of 5 sccm listed in the table for DMSe, the true flow rate is likely close to  $(0.34) \times 5 \text{ sccm} = 1.7 \text{ sccm}$ .

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The online version of the original article can be found under doi:[10.1007/s11090-010-9278-8](https://doi.org/10.1007/s11090-010-9278-8).

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